

CORRECTION

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DOI: 10.1039/c5ra90056e

www.rsc.org/advances

Correction: Using a functional C₈₄ monolayer to improve the mechanical properties and alter substrate deformation

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Correction for 'Using a functional C₈₄ monolayer to improve the mechanical properties and alter substrate deformation' by Wen-Jay Lee *et al.*, *RSC Adv.*, 2015, **5**, 47498–47505.

The authors regret that the incorrect institutional address was provided for Chih-Pong Huang in the original article. The correct institutional address, at which the work reported in the article was carried out, is shown herein as 'Materials & Electro-Optics Research Division, Chung-Shan Institute of Science and Technology, Taoyuan 325, Taiwan'.

Additionally, the name of institution 'd', with which Mon-Shu Ho is affiliated, was incorrectly presented in the original manuscript. 'Institutes of Nanoscience' should instead have been presented as 'Institute of Nanoscience'.

Finally, the location of institution 'b', with which Jyun-Hwei Tsai and Wan-Sheng Su are affiliated, was also incorrectly presented in the original manuscript. 'Hsinchhu' should instead have been presented as 'Hsinchu'.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.



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